

Applicant: TSE et al.

Filing Date: 28 February 2000

Group:

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| Examiner: | Date Considered: |
| LUN-SEE LAD | 12/9/03 |

EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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Attorney Docket No.:

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PCI-729

09/514,141

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(Use several sheets if necessary)

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Technology Center 2600

U.S. PATENT DOCUMENTS

| EXAMINER INITIAL | PATENT NUMBER | ISSUE DATE | PATENTEE | CLASS | SUB- CLASS | FILING DATE |
|---------------------|---------------|---------------|---------------|-------|---------------|----------------|
| L.S. | 4,199,295 | 22 Apr. 1980 | Raffy et al. | | | |
| L.S. | 5,801,341 | 01 Sep. 1998 | Newell et al. | | | |
| L.S. | 5,821,472 | 13 Oct. 1998 | Zwernemann | | | |
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FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

| EXAMINER INITIAL | DOCUMENT NUMBER | PUBLICATION DATE | COUNTRY OR PATENT OFFICE | CLASS | SUB- CLASS | TRANSLATION | |
|---------------------|-----------------|------------------|-----------------------------|-------|---------------|-------------|----|
| | | | | | | Yes | No |
| L.S. | 805,431 | 05 Nov. 1997 | EP | | | | |
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OTHER DOCUMENTS (Including Author, Title, Date, Relevant Pages, Place of Publication)

| EXAMINER INITIAL | |
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Examiner:

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